

Supplementary Information

Hydrogen-Bonded MXene Ohmic Contacts: Overcoming Schottky and Tunneling Barriers for Quantum-Limit 2D-MoS₂ Electronics

Weishu Chen[#], Tao Shen[#], Ji-Chang Ren^{} and Shuang Li^{*}*

^a Nano and Heterogeneous Materials Center, School of Materials Science and Engineering, Nanjing University of Science and Technology, Nanjing 210094, China.

[#] These authors contributed equally to this work.

Figure S1. (a) The projected band and density of states (DOS) diagrams for $\text{Ta}_3\text{C}_2\text{O}_2$ and (b) Ta_3C_2 heterostructures with MoS_2 under M-S stacking, where the gray scattered points in the projected band diagram represent the energy bands of the entire heterostructure, the red scattered points represent the energy bands of MoS_2 , the distance between the blue horizontal line and the Fermi level corresponds to the Schottky barrier (Φ_{SB}). The Fermi level is set at 0 eV, and ‘Total’ in the DOS diagram represents the entire heterostructure.

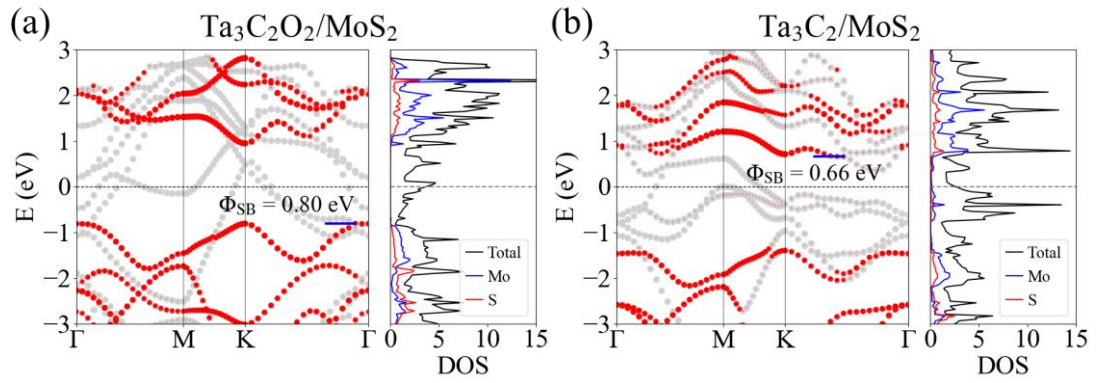
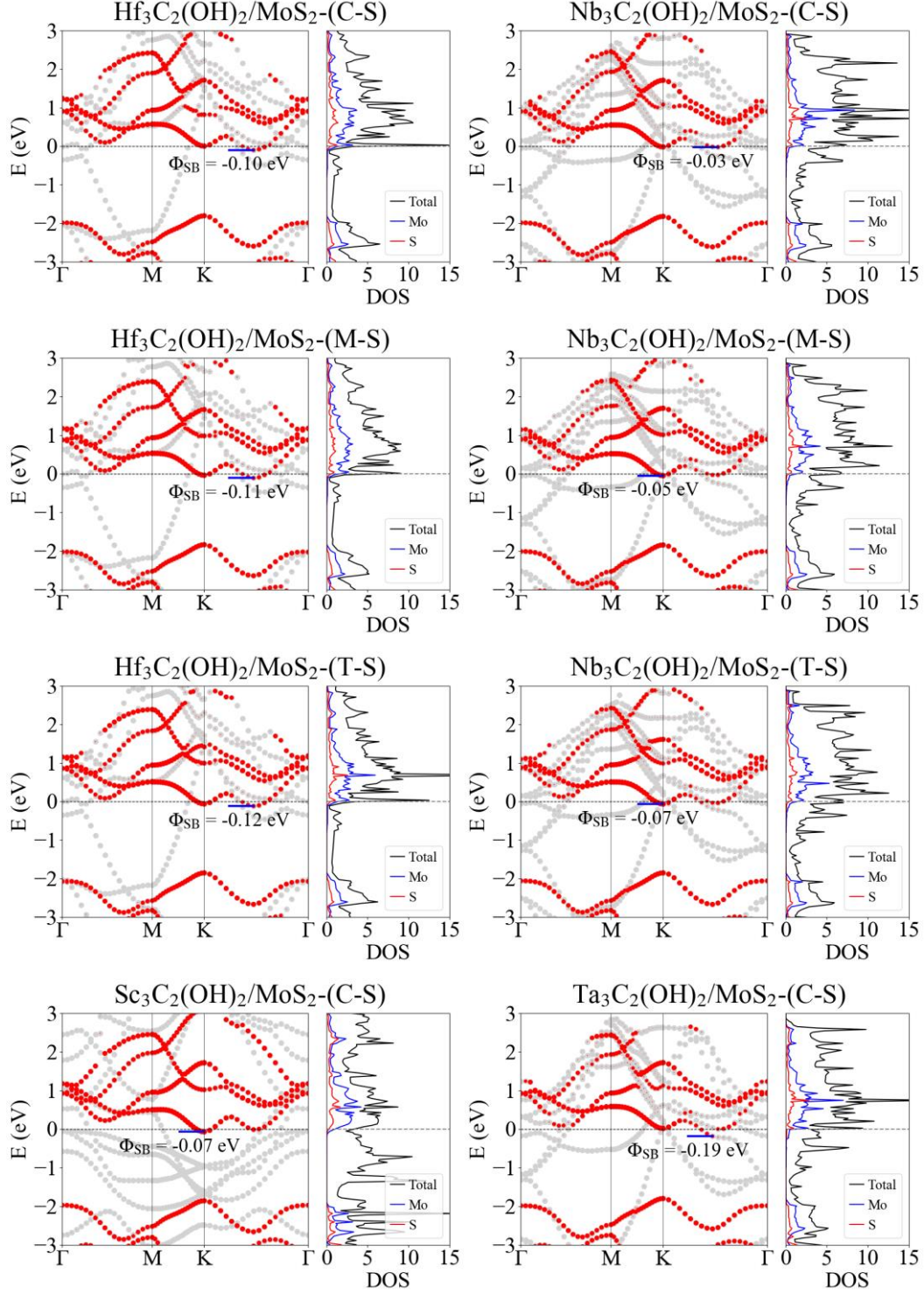
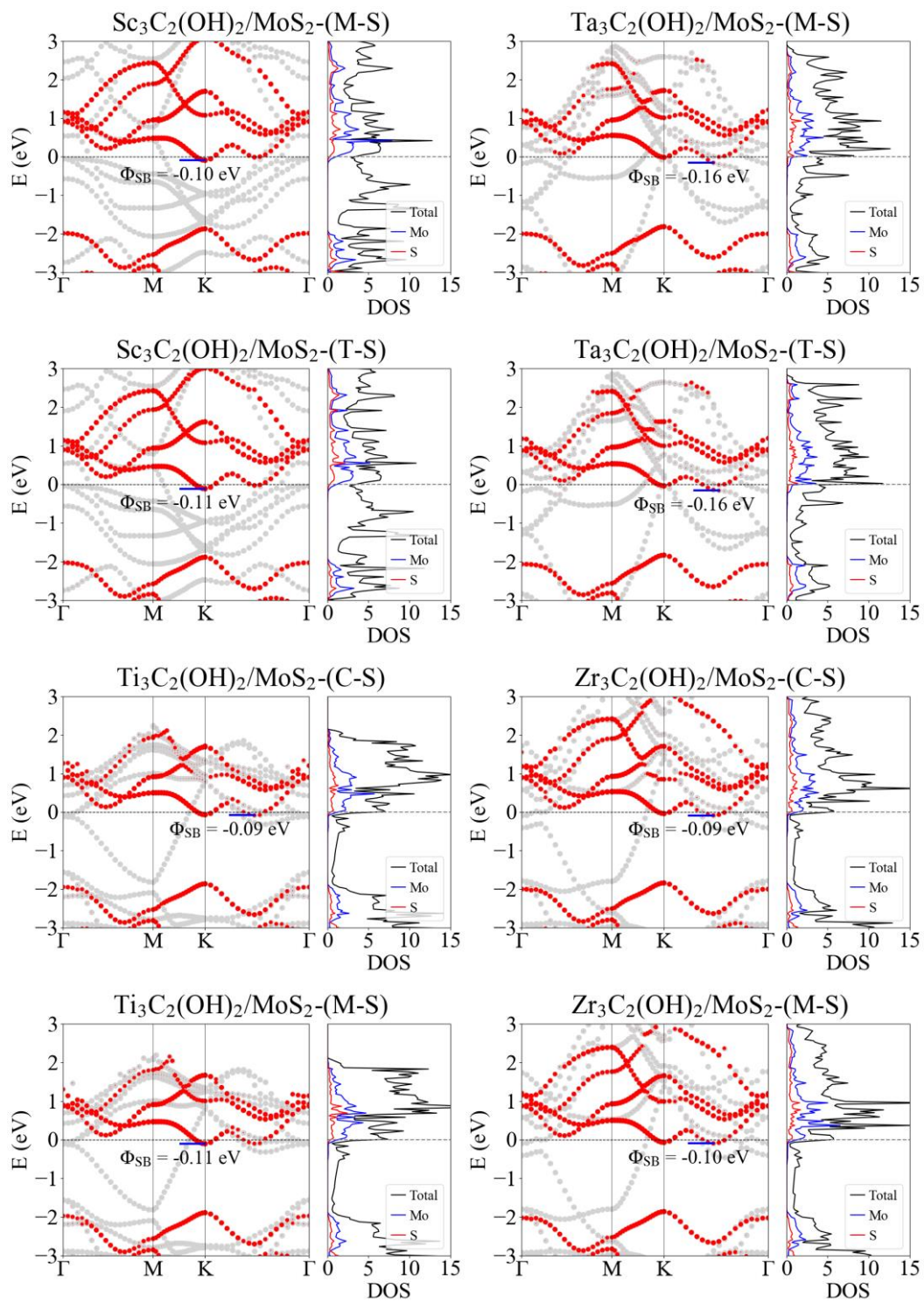


Figure S2. Projected band and DOS diagrams for the six types of $M_3C_2(OH)_2/MoS_2$ with three different stacking modes, with the corresponding parameters having the same meaning as in Figure S1.





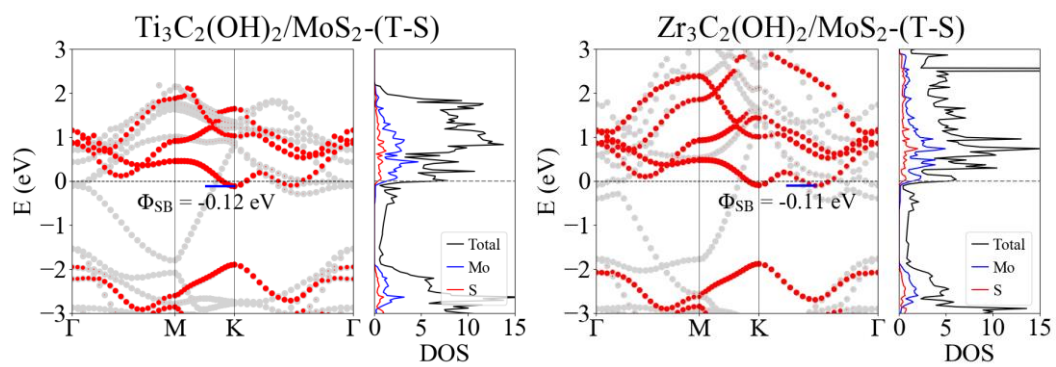
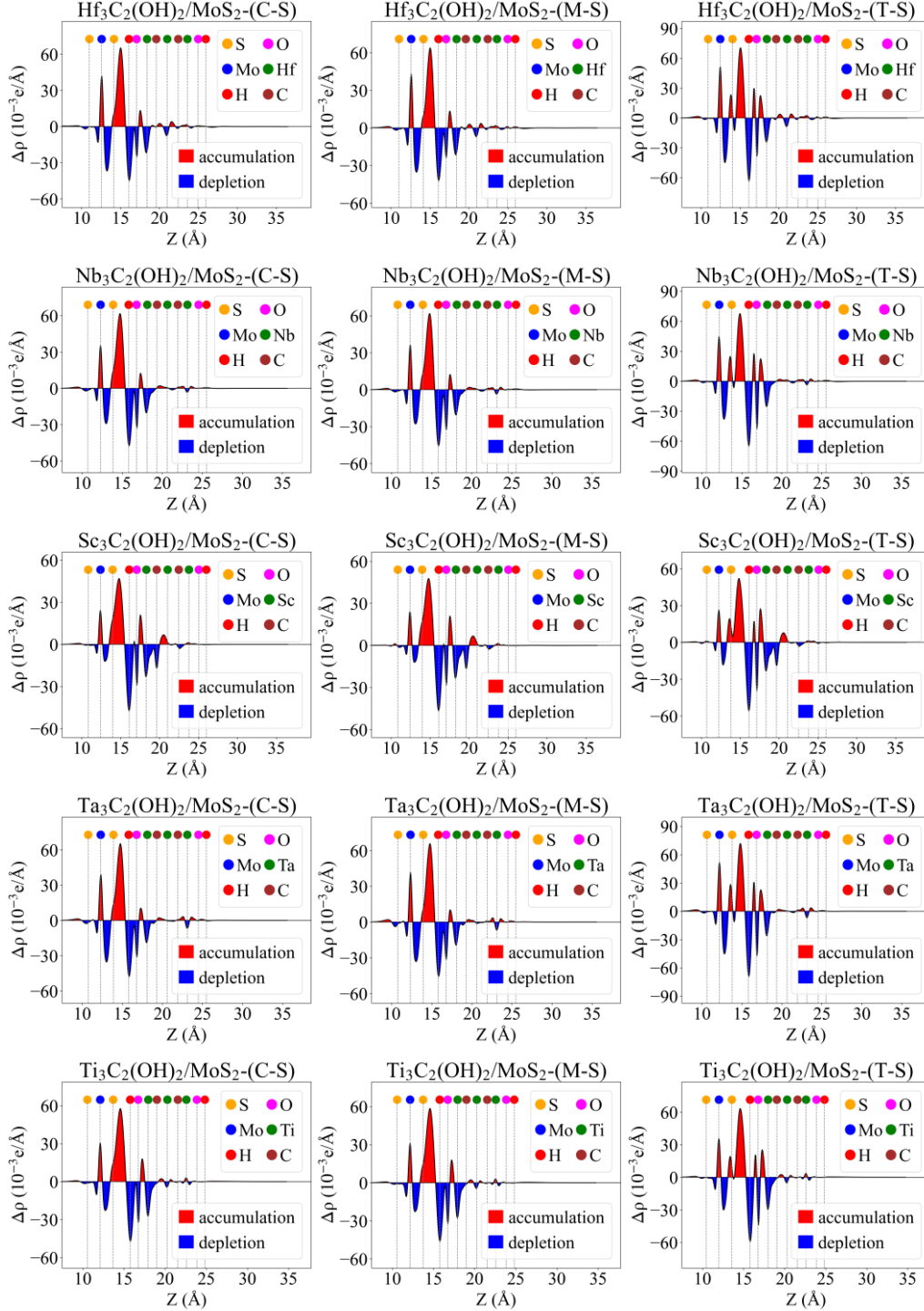


Figure S3. The plane differential charge density plots along the z-direction under three types of stacking structures for six types of $M_3C_2(OH)_2/MoS_2$. The red areas represent charge accumulation, while the blue areas represent charge depletion.



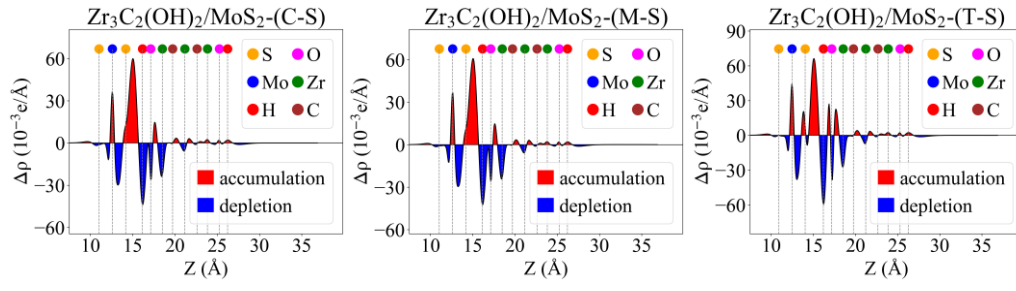


Figure S4. The electrostatic potential curves along the z-direction for: **(a)** $\text{Ta}_3\text{C}_2(\text{OH})_2$; **(b)** $\text{Ta}_3\text{C}_2\text{O}_2$; **(c)** Ta_3C_2 ; **(d)** $\text{Ta}_3\text{C}_2(\text{NH})_2$. The E_f represents the Fermi level, and the center of the red dashed box corresponds to the V_{eff} point of the bottommost atom.

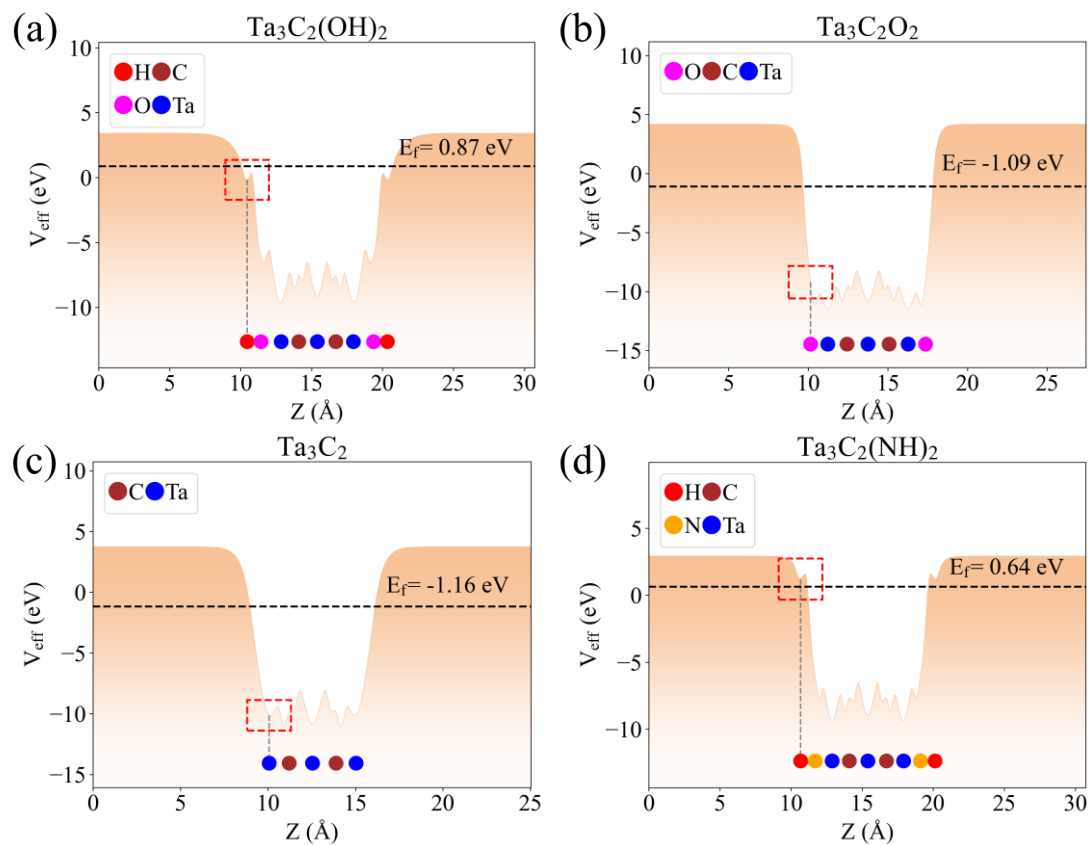


Figure S5. Projected band structures (a) with spin–orbit coupling (SOC) and (b) without SOC and electrostatic potential profiles along the z-direction (c) with SOC and (d) without SOC for the $\text{Ta}_3\text{C}_2(\text{OH})_2/\text{MoS}_2$ heterostructure. The parameters in the projected band structures have the same meanings as in Figure S1. In the electrostatic potential profiles, E_f represents the Fermi level. W_{TB} , Φ_{TB} , and Φ_{gap} denote the tunneling barrier width, height, and the peak value, respectively. The numbers at the ends of the vertical unidirectional arrows represent the V_{eff} of the interface H atom.

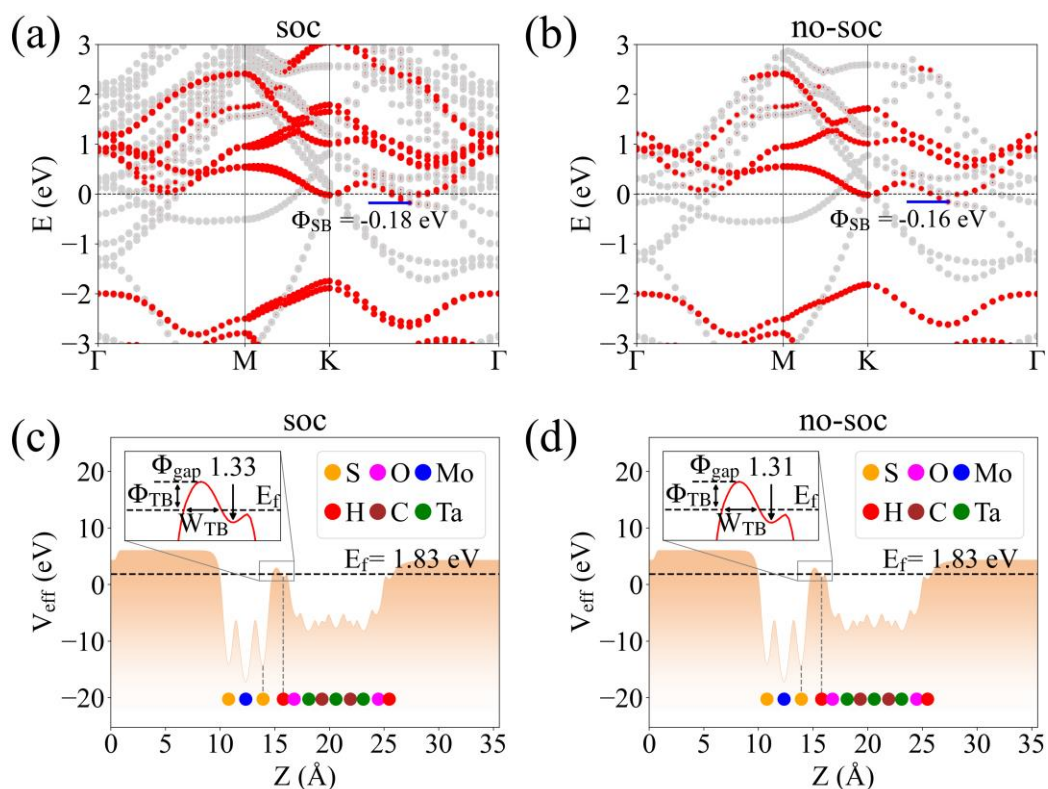


Figure S6. The tunneling probability (P_{TB}) of the $Ta_3C_2(OH)_2/MoS_2$ system based on the M-S model as a function of the interlayer spacing (d). In the legend, 0 is the reference object (d is 1.87 Å), and the others are based on increasing and decreasing d from this point.

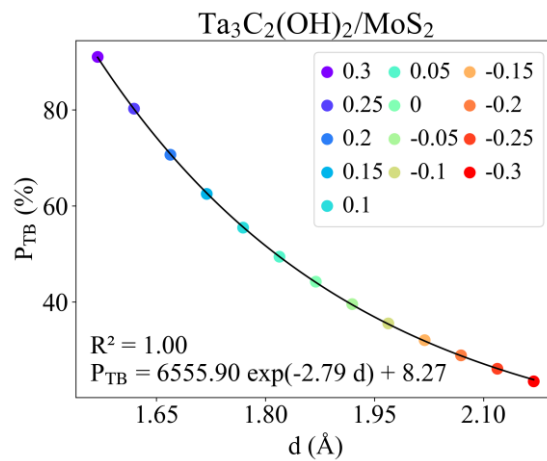


Figure S7. The electrostatic potential curves along the z-direction for 6 types of $M_3C_2(NH)_2/MoS_2$ and 6 types of $M_3N_2(NH)_2/MoS_2$ heterostructures. The corresponding parameter definitions are the same as those in Figure S5.

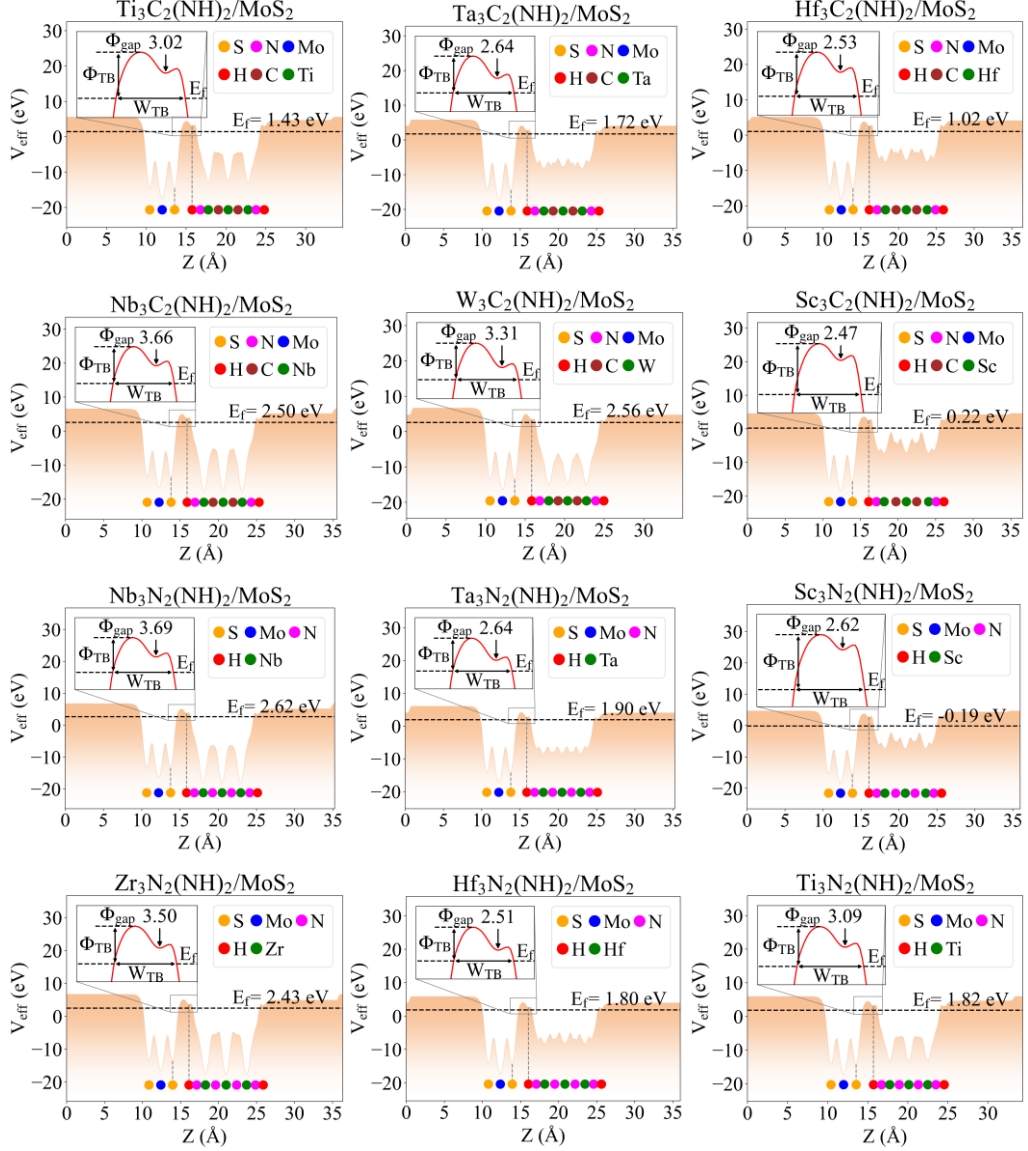


Figure S8. Relationship diagrams of tunneling probability versus (a) interlayer spacing and (b) binding energy for $M_3X_2(OH)_2/MoS_2$ ($X=C/N$) heterostructures.

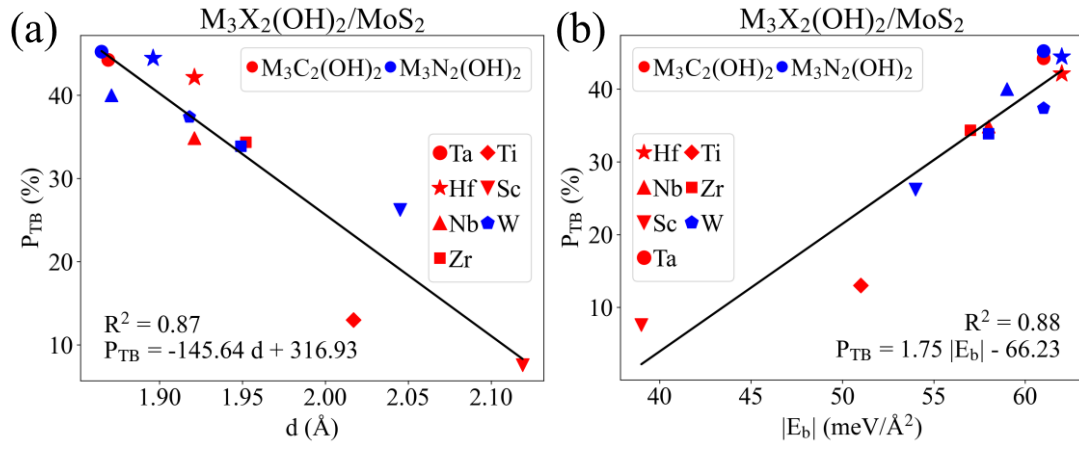


Figure S9. The electrostatic potential curves along the z-direction for the $\text{Ti}_3\text{C}_2(\text{OH})_2/\text{MoS}_2$ heterostructure under biaxial strain ranging from -2% to 2%. The corresponding parameter definitions are the same as those in Figure S5.

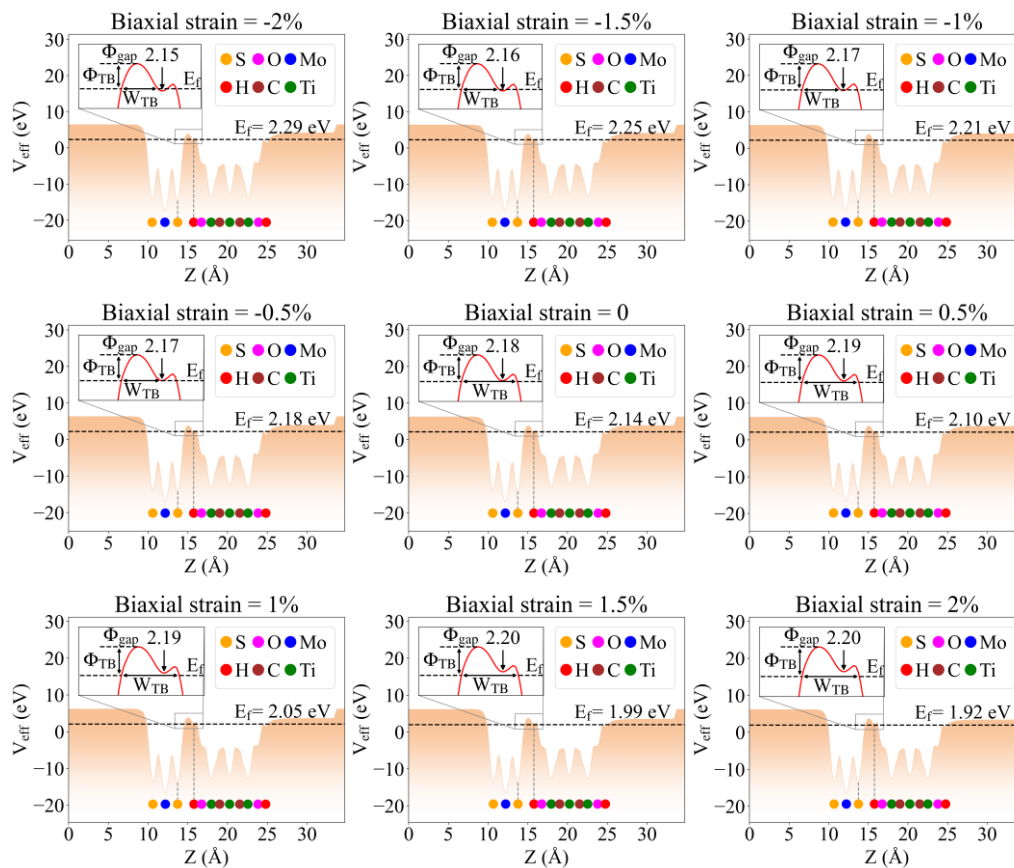


Figure S10. (a) Phonon spectrum of the $\text{Ti}_3\text{C}_2(\text{OH})_2/\text{MoS}_2$ heterostructure under -2% biaxial strain, and (b) temperature and (c) energy change diagrams during 10 ps of molecular dynamics simulation at 300 K.

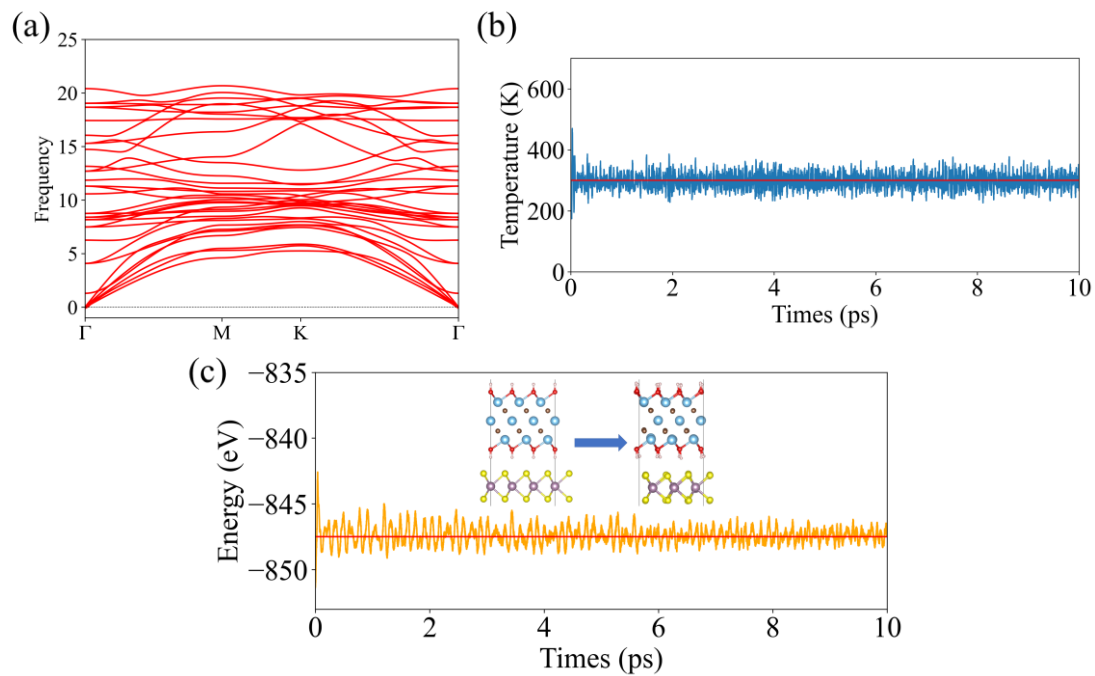


Figure S11. The variation of the band gap (gap) of MoS₂ and the Schottky barrier (Φ_n) at the Ti₃C₂(OH)₂/MoS₂ heterostructure under biaxial strain. The value of gap_0 is 1.76 eV, corresponding to the orange dashed line, and the purple dashed line corresponds to “ $\Phi_n = 0$ ”.

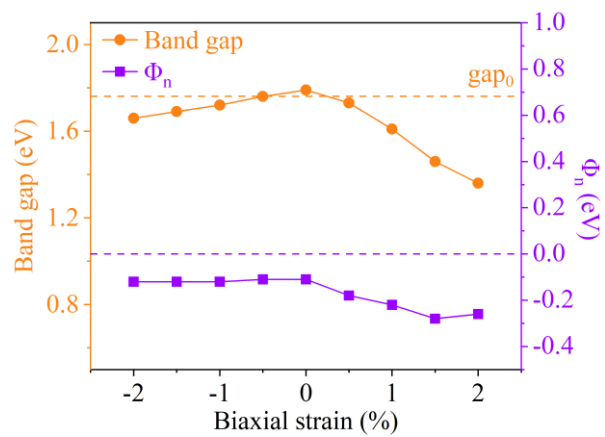


Table S1. Mismatch degrees (Mismatch) of six types of $M_3C_2(OH)_2/MoS_2$ heterostructures.

$M_3C_2(OH)_2/MoS_2$	Ti	Nb	Ta	Hf	Zr	Sc
Mismatch(%)	3.21	1.92	2.16	3.57	4.85	2.85

Table S2. Binding energy (E_b) and Schottky barrier (Φ_{SB}) for the three models of six types of $M_3C_2(OH)_2/MoS_2$ heterostructures.

MXene/MoS_2	Model	E_b (meV/$\text{\AA}^2$)	Φ_{SB} (eV)
$Hf_3C_2(OH)_2$	C-S	-61	-0.10
	M-S	-62	-0.11
	T-S	-65	-0.12
$Nb_3C_2(OH)_2$	C-S	-57	-0.03
	M-S	-58	-0.05
	T-S	-60	-0.07
$Ta_3C_2(OH)_2$	C-S	-61	-0.19
	M-S	-61	-0.16
	T-S	-65	-0.16
$Ti_3C_2(OH)_2$	C-S	-50	-0.09
	M-S	-51	-0.11
	T-S	-53	-0.12
$Zr_3C_2(OH)_2$	C-S	-56	-0.09
	M-S	-57	-0.10
	T-S	-60	-0.11
$Sc_3C_2(OH)_2$	C-S	-38	-0.07
	M-S	-39	-0.10
	T-S	-39	-0.11

Table S3. Comparative electronic properties of Ta₃C₂(OH)₂/MoS₂ heterostructure with and without spin-orbit coupling (SOC): tunneling barrier height (Φ_{TB}), width (W_{TB}), probability (P_{TB}), impedance (ρ_{T}), effective potential at interface H (V_{H}), and Fermi level (E_{f}).

	$W_{\text{TB}}(\text{\AA})$	$\Phi_{\text{TB}}(\text{eV})$	$P_{\text{TB}}(\%)$	$\rho_{\text{T}} (\text{e}^{-9} \Omega\text{cm}^2)$	$V_{\text{H}}(\text{eV})$	$E_{\text{f}}(\text{eV})$
SOC	0.77	1.11	43.66	0.035	1.33	1.83
no-SOC	0.76	1.09	44.24	0.035	1.31	1.83

Table S4. The tunneling barrier width (W_{TB}), height (Φ_{TB}), tunneling probability (P_{TB}), tunneling impedance (ρ_T), and interlayer spacing (d) after structural optimization for three models of $M_3C_2(OH)_2/MoS_2$ heterostructures.

MXene/MoS_2	model	$W_{TB}(\text{\AA})$	$\Phi_{TB}(\text{eV})$	$P_{TB}(\%)$	$\rho_T(10^{-9} \Omega \text{ cm}^2)$	$d(\text{\AA})$
$Ta_3C_2(OH)_2$	C-S	0.80	1.20	40.61	0.038	1.89
	M-S	0.76	1.09	44.24	0.035	1.87
	T-S	0.98	1.59	28.20	0.058	2.06
$Hf_3C_2(OH)_2$	C-S	0.80	1.17	41.00	0.038	1.92
	M-S	0.79	1.14	42.15	0.037	1.92
	T-S	1.00	1.61	27.26	0.061	2.10
$Nb_3C_2(OH)_2$	C-S	0.93	1.40	32.61	0.051	1.94
	M-S	0.89	1.32	34.86	0.047	1.92
	T-S	1.11	1.79	21.77	0.080	2.12
$Zr_3C_2(OH)_2$	C-S	0.95	1.43	31.21	0.054	1.99
	M-S	0.90	1.33	34.35	0.048	1.95
	T-S	1.13	1.80	21.22	0.084	2.15
$Ti_3C_2(OH)_2$	C-S	1.62	1.72	11.38	4.31	2.06
	M-S	1.57	1.61	13.01	15.54	2.02
	T-S	1.80	2.03	7.24	2.31	2.22
$Sc_3C_2(OH)_2$	C-S	1.76	2.09	7.42	2.24	2.13
	M-S	1.75	2.07	7.59	2.26	2.12
	T-S	1.96	2.41	4.38	2.53	2.32

Table S5. The mismatch, Φ_{SB} , and E_{b} of $\text{M}_3\text{X}_2\text{T}_2/\text{MoS}_2$ ($\text{X}=\text{N}$, $\text{T}=\text{OH}/\text{NH}$; $\text{X}=\text{C}$, $\text{T}=\text{NH}$) heterostructures.

MXene/MoS₂	Mismatch(%)	Φ_{SB} (eV)	E_{b} (meV/Å²)
Hf ₃ N ₂ (OH) ₂	0.32	-0.09	-62
Nb ₃ N ₂ (OH) ₂	2.50	-0.02	-59
Sc ₃ N ₂ (OH) ₂	1.06	-0.09	-54
Ta ₃ N ₂ (OH) ₂	3.26	-0.04	-61
W ₃ N ₂ (OH) ₂	1.85	-0.06	-61
Zr ₃ N ₂ (OH) ₂	1.95	-0.06	-58
Hf ₃ C ₂ (NH) ₂	3.77	-0.06	-32
Nb ₃ C ₂ (NH) ₂	0.21	0.01	-35
Sc ₃ C ₂ (NH) ₂	4.94	0.19	-27
Ta ₃ C ₂ (NH) ₂	0.22	-0.09	-37
Ti ₃ C ₂ (NH) ₂	3.72	-0.02	-29
W ₃ C ₂ (NH) ₂	2.60	-0.07	-39
Hf ₃ N ₂ (NH) ₂	2.49	-0.13	-38
Nb ₃ N ₂ (NH) ₂	1.56	-0.03	-37
Sc ₃ N ₂ (NH) ₂	2.57	0.79	-27
Ta ₃ N ₂ (NH) ₂	1.28	-0.05	-40
Ti ₃ N ₂ (NH) ₂	4.83	-0.07	-32
Zr ₃ N ₂ (NH) ₂	3.83	-0.10	-35

Table S6. The W_{TB} , Φ_{TB} , P_{TB} , ρ_T , and d for $M_3X_2T_2/\text{MoS}_2$ heterostructures.

MXene/MoS₂	$W_{TB}(\text{\AA})$	$\Phi_{TB}(\text{eV})$	$P_{TB}(\%)$	$\rho_T(10^{-9} \Omega \text{ cm}^2)$	$d(\text{\AA})$
Ta ₃ N ₂ (OH) ₂	0.74	1.08	45.24	0.033	1.87
Hf ₃ N ₂ (OH) ₂	0.76	1.09	44.47	0.035	1.90
Nb ₃ N ₂ (OH) ₂	0.82	1.19	40.01	0.040	1.87
W ₃ N ₂ (OH) ₂	0.86	1.26	37.39	0.043	1.92
Zr ₃ N ₂ (OH) ₂	0.90	1.36	33.86	0.048	1.95
Sc ₃ N ₂ (OH) ₂	1.04	1.57	26.22	0.067	2.05
W ₃ C ₂ (NH) ₂	1.77	2.30	6.36	2.13	2.13
Ta ₃ C ₂ (NH) ₂	1.78	2.35	6.14	2.11	2.11
Nb ₃ C ₂ (NH) ₂	1.78	2.41	5.89	2.10	2.10
Hf ₃ C ₂ (NH) ₂	1.89	2.78	4.00	2.37	2.17
Ti ₃ C ₂ (NH) ₂	1.94	2.90	3.40	2.59	2.21
Sc ₃ C ₂ (NH) ₂	1.97	3.36	2.49	2.97	2.17
Ta ₃ N ₂ (NH) ₂	1.72	2.23	7.16	2.11	2.08
Hf ₃ N ₂ (NH) ₂	1.75	2.25	6.80	2.12	2.12
Nb ₃ N ₂ (NH) ₂	1.76	2.42	6.03	2.07	2.08
Zr ₃ N ₂ (NH) ₂	1.83	2.55	5.00	2.19	2.15
Ti ₃ N ₂ (NH) ₂	1.85	2.63	4.62	2.24	2.16
Sc ₃ N ₂ (NH) ₂	2.06	3.90	1.56	4.07	2.20

Table S7. The W_{TB} , Φ_{TB} , P_{TB} , ρ_T , the MoS₂ bandgap (gap), Φ_{SB} , d and E_b of Ti₃C₂(OH)₂/MoS₂ heterostructures under a biaxial strain range from -2% to 2%.

Biaxial strain (%)	W_{TB} (Å)	Φ_{TB} (eV)	P_{TB} (%)	ρ_T ($10^{-9}\Omega$ cm²)	gap (eV)	Φ_{SB} (eV)	d (Å)	E_b (meV/ Å²)
-2	1.02	1.55	27.10	0.064	1.66	-0.12	2.02	-54.5
-1.5	1.06	1.59	25.55	0.069	1.69	-0.12	2.03	-53.6
-1	1.08	1.60	24.61	0.073	1.72	-0.12	2.02	-52.6
-0.5	1.11	1.57	24.10	0.077	1.76	-0.11	2.00	-51.7
0	1.57	1.61	13.01	15.54	1.79	-0.11	2.02	-51.0
0.5	1.59	1.66	12.20	6.51	1.73	-0.18	2.03	-50.4
1	1.62	1.73	11.27	4.12	1.61	-0.22	2.05	-50.0
1.5	1.60	1.72	11.73	4.92	1.46	-0.28	2.01	-49.8
2	1.61	1.78	11.13	3.85	1.36	-0.26	2.01	-49.7